A Perpendicular Spin Torque Switching based MRAM for the 28 nm Technology Node

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Outline

Perpendicular Spin Torque (P-ST) based MRAM
 A New Concept

Assessment for 28 nm Node
Data Retention
Low Switching Currents
Cell to Cell Interaction
Barrier Reliability

Cell Layout

Read Analysis

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Conventional MRAM



• WRITE:

Word/Bit line field used to set magnetic free layer

• READ:

Electrical determination of R by sense amplifiers

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Spin Torque Select-Based MRAM



Writing is done by a critical select current

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Perpendicular Anisotropy



Perpendicular anisotropy is very high

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Realization



Source: "Spin transfer switching in TbCoFe / CoFeB / MgO / CoFeB / TbCoFe magnetoresistive tunneling junctions with perpendicular magnetic anisotropy", M. Nakayama et al., BB-09, 52nd Magnetism and Magnetic Materials Conference (MMM) in Tampa, Nov. 2007

Feasibility of concept is demonstrated MTJ stack engineering is important

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Scalability of Activation Energy



High anisotropy ensures scaling below 20 nm

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Scalability of Switching Current



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Cell to Cell Interaction



Significantly reduced stray field interaction

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Impact of Interaction on E_a



structural cell size [F^2 with F = 28 nm]

High data retention at dense spacing

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Reliability Estimates



P-ST allows to use high RA for reliable operation

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Cell Layout at 28 nm Node



6 F² layout ensures sufficient current drivability

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Read Disturb



At $I_c \sim 30 \ \mu\text{A}$ a read current of $I_r \sim 10 \ \mu\text{A} (\gamma \sim 0.3)$ is feasible without read disturb

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MTJ Stack Performance

Measured magneto resistance (MR) for in-plane systems



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Read Circuit



Typical: $R_0 = 6 \ k\Omega$ $R_1 = 12 \ k\Omega$ $R_{para} = 14 \ k\Omega$

Current compliance avoids read disturb

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Read Operation Simulation



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Summary

Perpendicular Spin Torque has been studied targeting the 28 nm node.

Expected benefits are:

- Iong data retention (> 10 yrs @ 85°C)
- Iow write current (~ 30 μA)
- small cell sizes (~ 6 F²)
- high write endurance and no read disturb

Random access speeds are 30 ns for read and 10 ns for write.

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